



Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 287990US2PCT		SERIAL NO. 10/572,353	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT Jean-Charles GUIBERT			
				FILING DATE March 16, 2006		GROUP	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA	2003/0104287	6/5/2003	YUASA, Mitsuhiro			
	AB	6 416 908	7/9/2002	KLOSNER, Marc A. et al.			
	AC	6 375 870	4/23/2002	VISOVSKY, Nick J. et al.			
	AD	5 281 511	1/25/1994	GERHARDT, Joergen			
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
	AO	199 13 683	11/25/1999	DE(equivalent of US 6 455 429)			NO
	AP	0 845 710	8/3/1998	EP(with English abstract)			NO
	AQ						
	AR						
	AS						
	AT						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)							
	AU	RUCHHOEFT, P. et al., "Patterning curved surfaces: Template generation by ion beam proximity lithography and relief transfer by step and flash imprint lithography", Journal of Vacuum Science and Technology, Vol. 17, No. 6, Pages 2965-2969, 1999.					
	AV	ROGERS, J.A. et al., "Printing, molding, and near-field photolithographic methods for patterning organic lasers, smart pixels and simple circuits", Synthetic Metals, Vol. 115, No. 1-3, Pages 5-11, 2000.					
	AW	ROOS, Nils et al., "Nanoimprint Lithography with a Commercial 4 Inch Bond System for Hot Embossing ", Proceedings of The SPIE, Vol. 4343, Pages 427-435, 2001.					
	AX	CHOU, Stephen Y. et al., "Imprint of sub-25 nm Vias and trenches in polymers", Appl. Phys. Lett. Vol. 67, No. 21, Pages 3114-3116, 20 November 1995.					
	AY	TAN, Hua et al., "Roller nanoimprint lithography", J. Vac. Sci. Technol. Vol. 16, No. 6, Pages 3926-3928, 1998.					
	AZ	GUIBERT, Jean-Charles, "Nanotechnologies and nanolithography in Europe", Pages xxi-xxx.					<input type="checkbox"/> Additional References sheet(s) attached
Examiner /Jonathan Jelsma/					Date Considered 03/18/2009		
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							